Notice of References Cited Application/Control No. | Applicant(s)/Patent Under Reexamination TAKATA ET AL. | Examiner | Art Unit | Page 1 of 1 U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	Α	US-6,479,210	11-2002	Kinoshita et al.	430/270.1
*	В	US-6,753,128	06-2004	Lee et al.	430/270.1
	С	US-			
	D	US-			
	ш	US-			
	F	US-			
	G	US-			
	Ι	US-	,		
	_	US-			
	J	US-			
	К	US-			
	L	US-			
	М	US-			

FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

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	*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
		U	
		'/	Wakisaka, T. et al. Development of Advanced ArF Resist Using Alicyclic Methacrylate Copolymer,SPIE,3999,2000,1088-1099.
		w	
		х	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)

Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.